

Modulated photoluminescence for lifetime determination in passivated crystalline silicon wafers

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Overview

- Lifetime measurement
- Modulated Photoluminescence (MPL)
 - Concept
 - Experimental setup
- Some results
- Summary

Lifetime measurement

Established methods:

- **Microwave photoconductance decay (μ -PCD)**
- **Quasi-steady-state photoconductance (QSSPC)**

Problem: high concentration of free carriers (metallic defects, metallic rear contacts, high doped layers)

→ conductive methods fail because of shielding effects

→ alternative method: MPL

Concept: MPL

Δn : excess carrier density
 G : generation rate
 R : recombination rate

- rate equation

$$\frac{d \Delta n}{dt} = G(t) - R(t)$$

- modulated generation rate:

$$G(t) = G_0 + G_1 e^{i\omega t} \quad G_0 = R = \frac{\Delta n_0}{\tau_n}$$

- Ansatz:

$$\Delta n(t) = \Delta n_0 + \Delta n_1 e^{i\omega t} \quad \Delta n_1(\varphi) = |\Delta n_1| e^{i\varphi}$$

→ amplitude:

$$|\Delta n_1| = \frac{\tau_n G_1}{\sqrt{1 + (\omega \tau_n)^2}}$$

→ phase shift:

$$\varphi = -\arctan(\omega \tau_n)$$

lifetime τ_n

Concept: MPL

$$Y_{PL} \propto R_{rad} \propto np$$

$$np = (n_0 + \Delta n)(p_0 + \Delta p)$$

$$p_0 \gg n_0 \approx \Delta n (p_0 + \Delta p) \approx$$

$$\text{(case 1)} \quad p_0 \gg \Delta n \approx \Delta n p_0$$

$$\text{(case 2)} \quad p_0 \ll \Delta n = \Delta p \approx \Delta n^2$$

assume $\tau \propto G^\beta$



$$Y_{PL} \propto G^\gamma = G^{\beta+1}$$

$$Y_{PL} \propto G^\gamma = G^{2\beta+2}$$

Y_{PL} : Luminescence yield

n, p : carrier densities

$\Delta p = \Delta n$: excess densities

p_0, n_0 : thermal eq. conc.

$(d/dx)=0$

Excess density proportional to lifetime: $\Delta n = G \tau_{eff}$

Concept: MPL

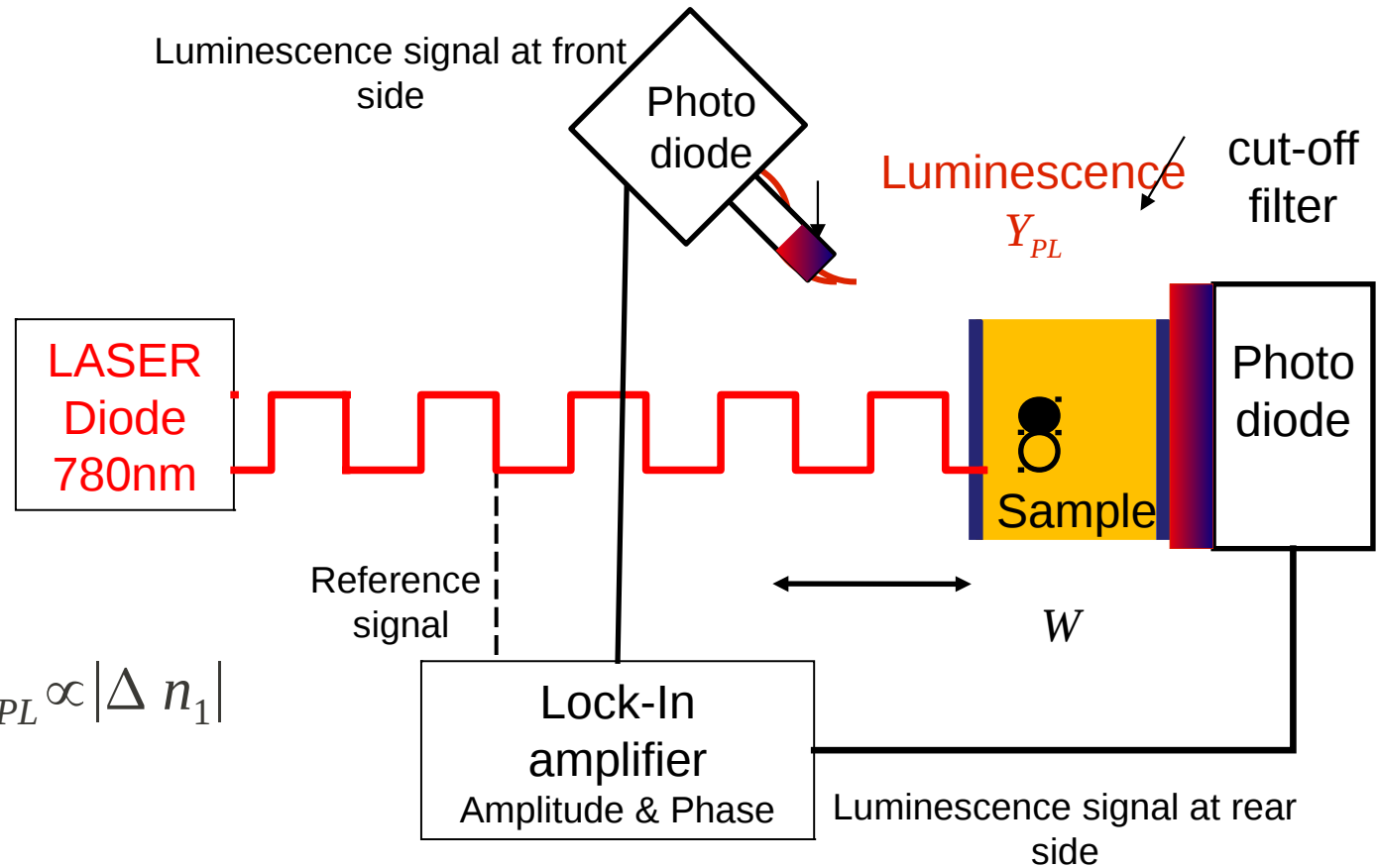
Considering high quality wafers with high bulk lifetime, the effective lifetime is determined by the contribution of surface/passivation layers (recombination velocities):

$$\frac{1}{\tau_{eff}} = \frac{1}{\tau_{bulk}} + \frac{S_{front}}{W} + \frac{S_{back}}{W} = \frac{1}{\tau_{bulk}} + \frac{2S}{W} \quad (\text{symmetrical samples})$$

$$\frac{1}{\tau_{bulk}} = \frac{1}{\tau_{defect}} + \frac{1}{\tau_{Aug}} + \frac{1}{\tau_{rad}}$$

S: recombination velocities
W: wafer thickness

Experimental setup



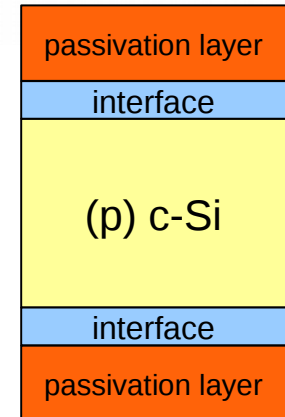
Amplitude: $Y_{PL} \propto |\Delta n_1|$

Phase: φ

Measurement at front and back side of sample possible

Samples

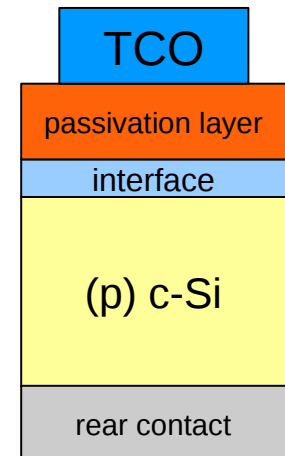
p-type c-Si wafer with different passivation:



- different passivation layers: n-type, intrinsic, SiC, a-Si:H, SiN

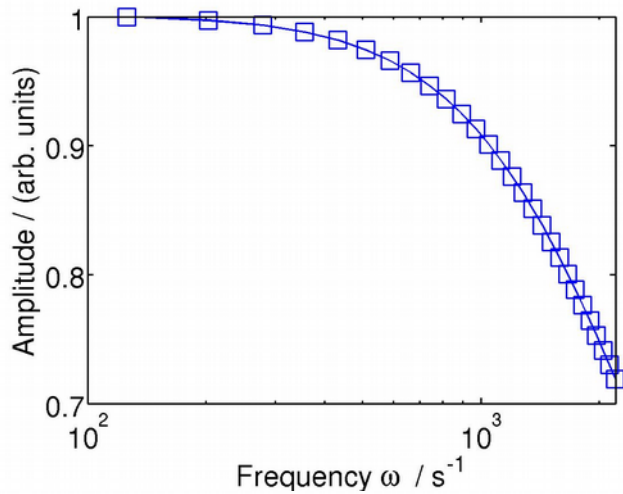
- different doping ($N_A=10^{15} \text{ cm}^{-3}$, $N_A=10^{16} \text{ cm}^{-3}$)

- wafer with TCO and rear contact (solar cell)

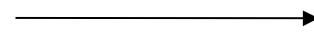


Results: SiC-passivation (1 Ωcm)

two procedures for lifetime extraction from experimental measurement

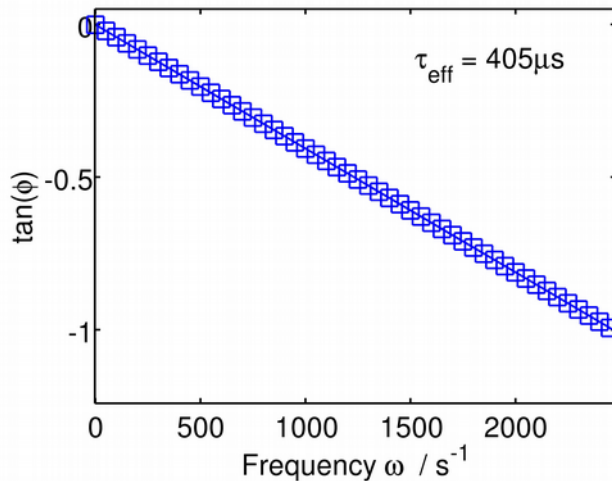


fit amplitude

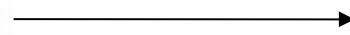


$$\tau_n = 397 \mu\text{s}$$

$$|\Delta n_1| = \frac{\tau_n G_1}{\sqrt{1 + (\omega \tau_n)^2}}$$



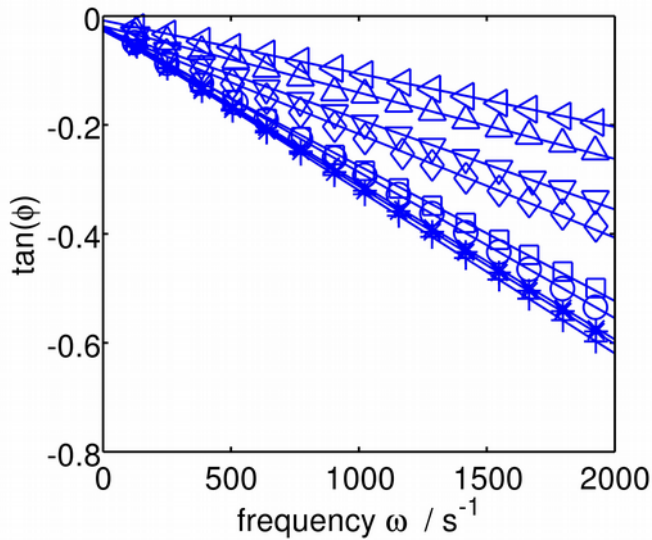
fit tangent



$$\tau_n = 405 \mu\text{s}$$


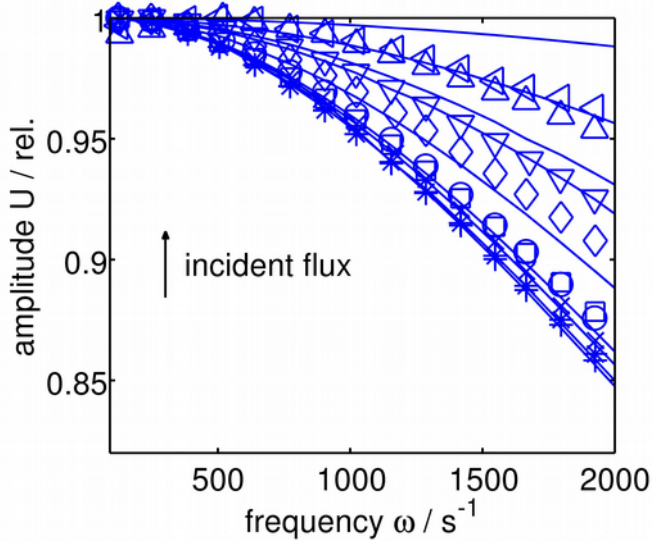
$$\tan(\varphi) = -\omega \tau_n$$

Results: SiN passivation (1 Ωcm)

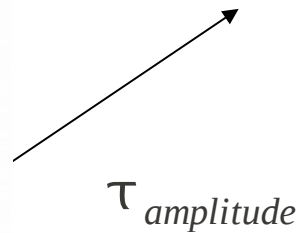
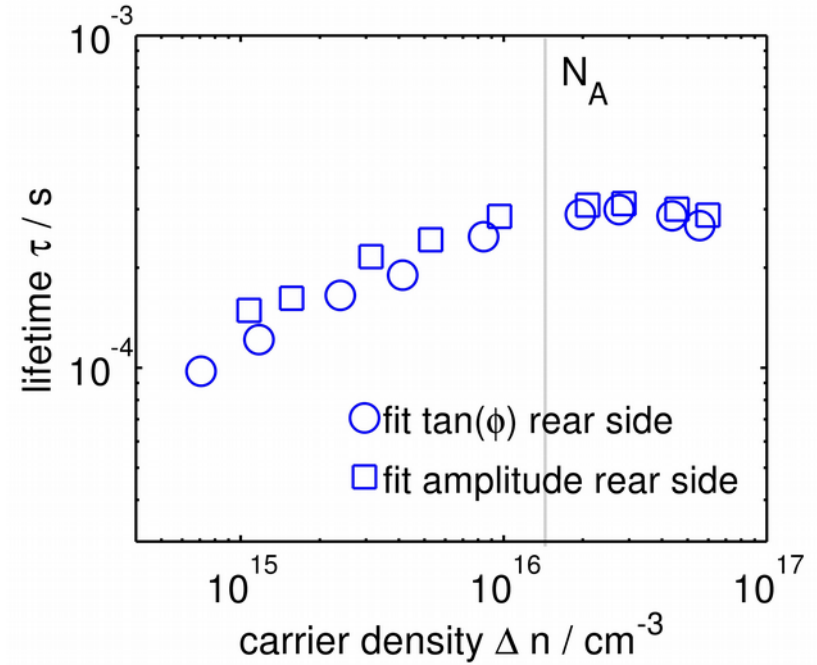


lifetime measurement by phase more reliable in contrast to amplitude

τ_ϕ

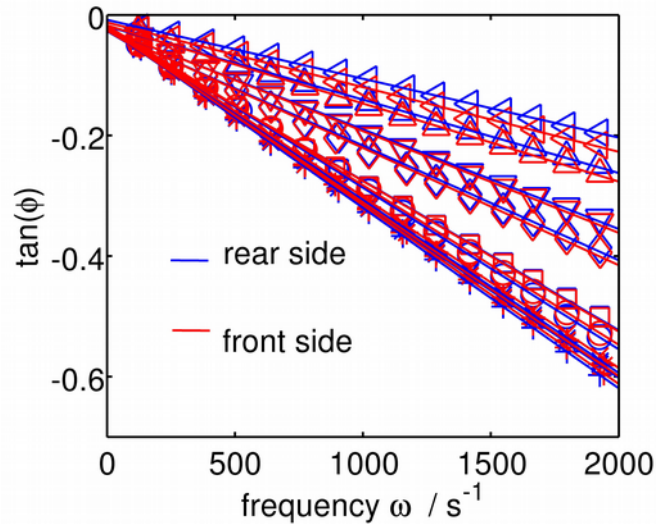



$\tau_{\text{amplitude}}$

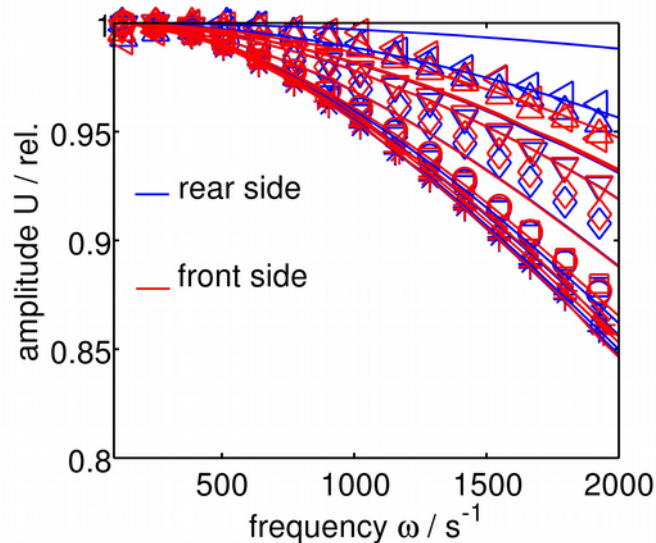
$$\Delta n = G \tau_{\text{eff}}$$

Results: SiN passivation (1 Ωcm)

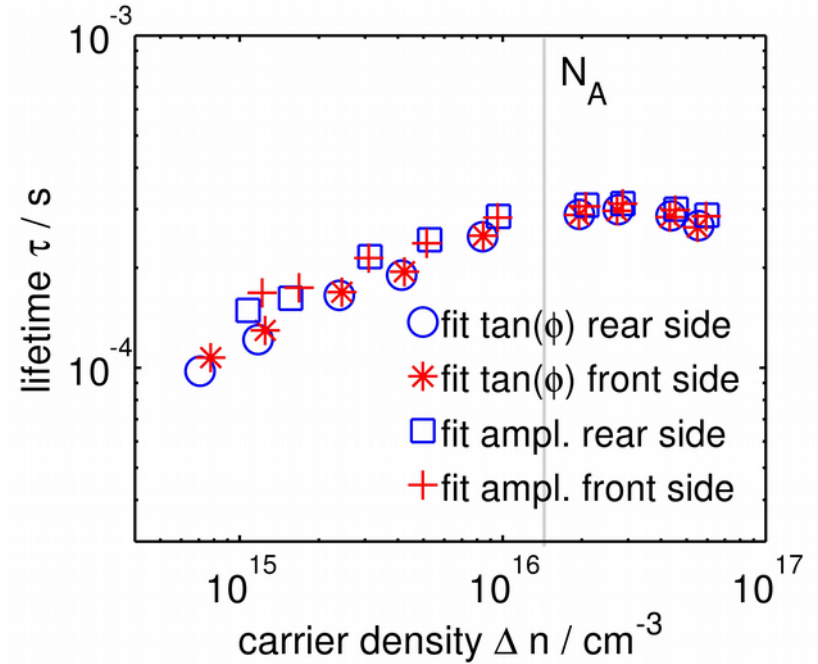


good agreement between measurement at rear and front side

τ_ϕ



$\tau_{\text{amplitude}}$

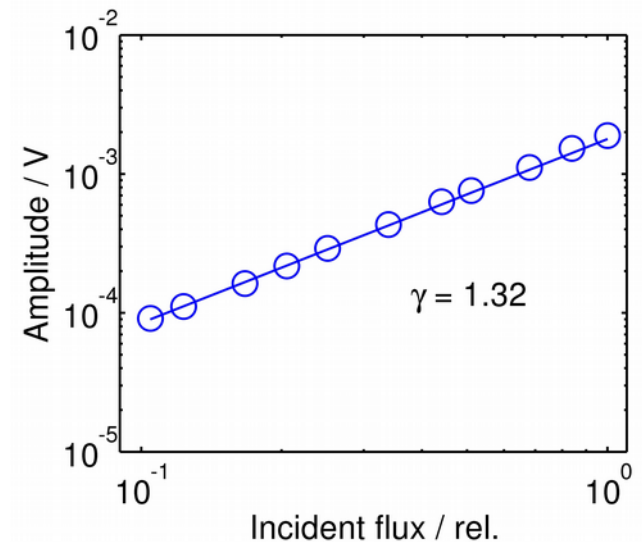
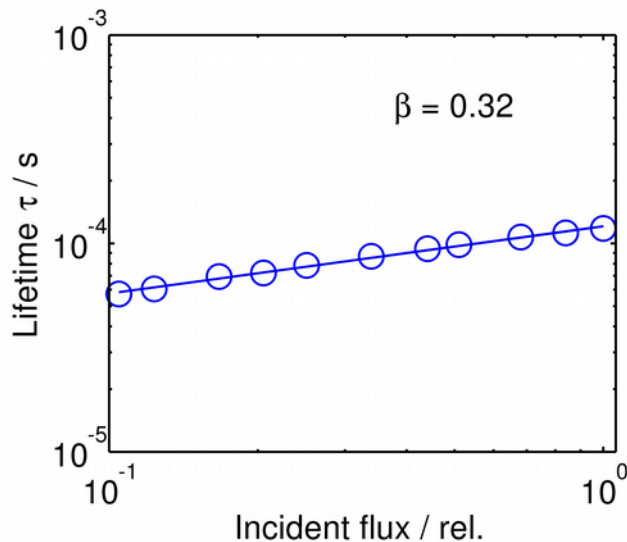


$$\Delta n = G \tau_{\text{eff}}$$

Results: (i)a-Si:H passivation (1 Ωcm)

Lifetime and amplitude depend on incident flux by power law (in regimes of high doping)

Power-law relation between lifetime and amplitude



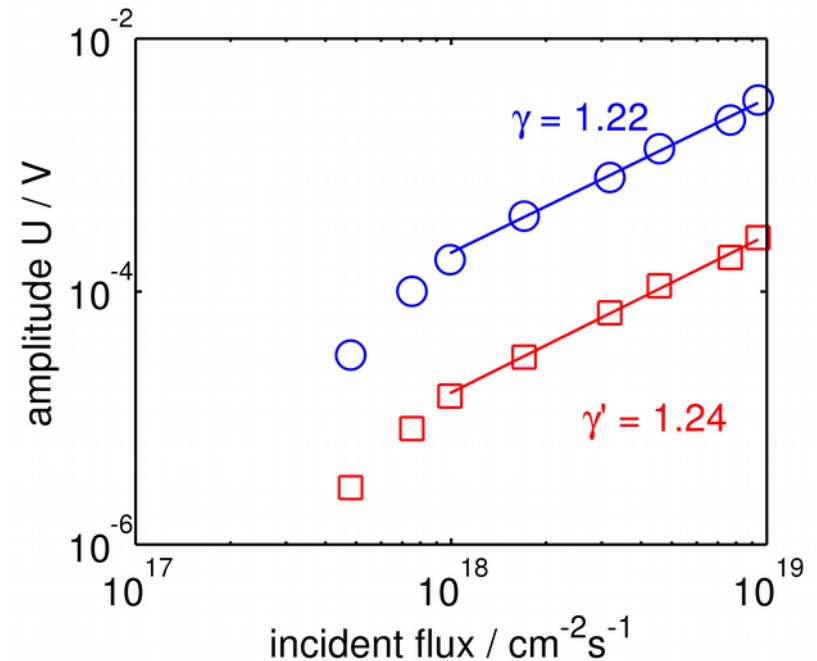
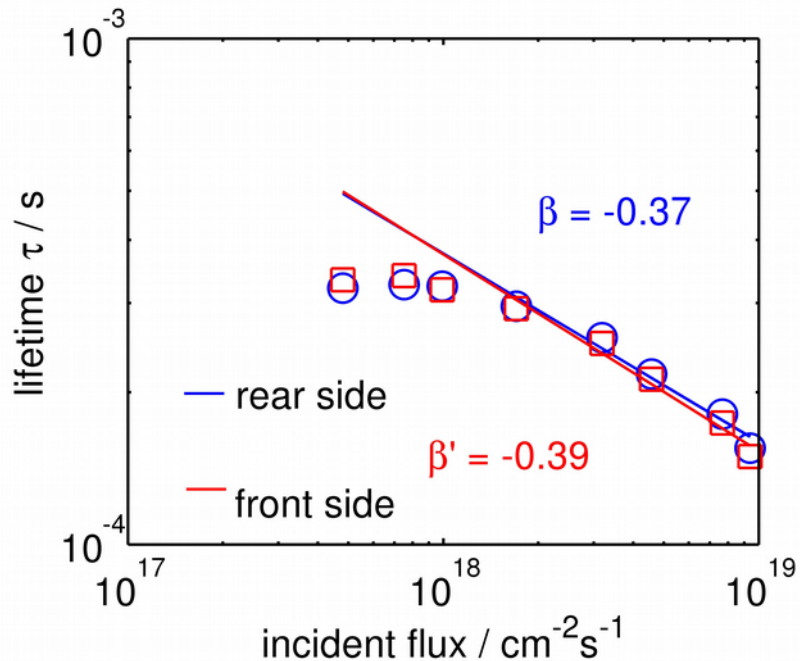
$$\tau \propto G^\beta \quad \longleftrightarrow \quad Y_{PL} \propto G^\gamma$$

$\gamma = 1 + \beta$

Results: (i)a-Si:H/(n)a-Si:H pass. (14 Ωcm)

Sample with low doping ($N_A = 10^{15}\text{cm}^{-3}$) \rightarrow in regimes of high excitation the powerlaw-relation between lifetime and amplitude is described by

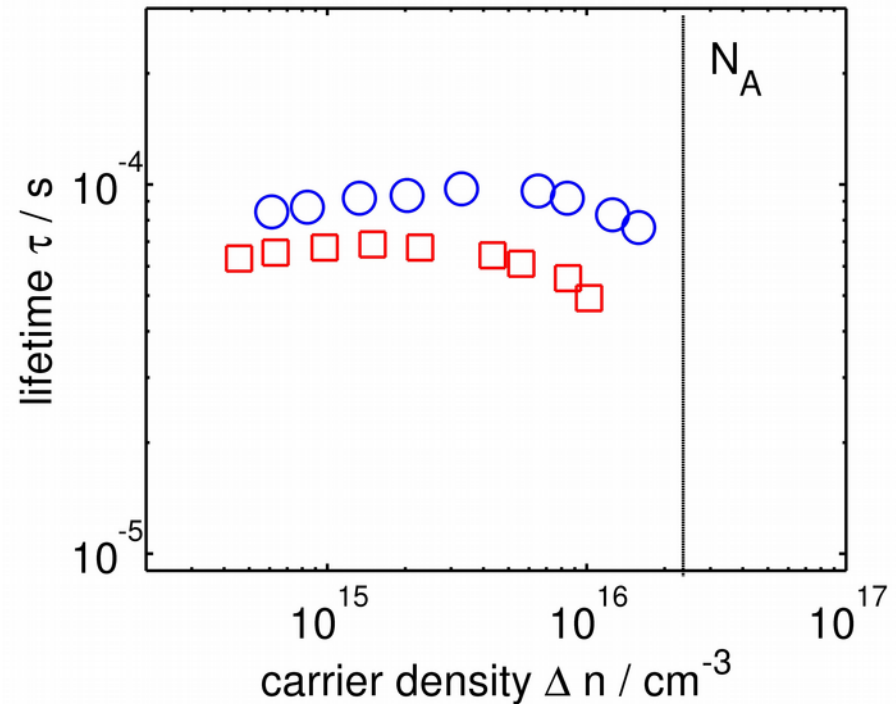
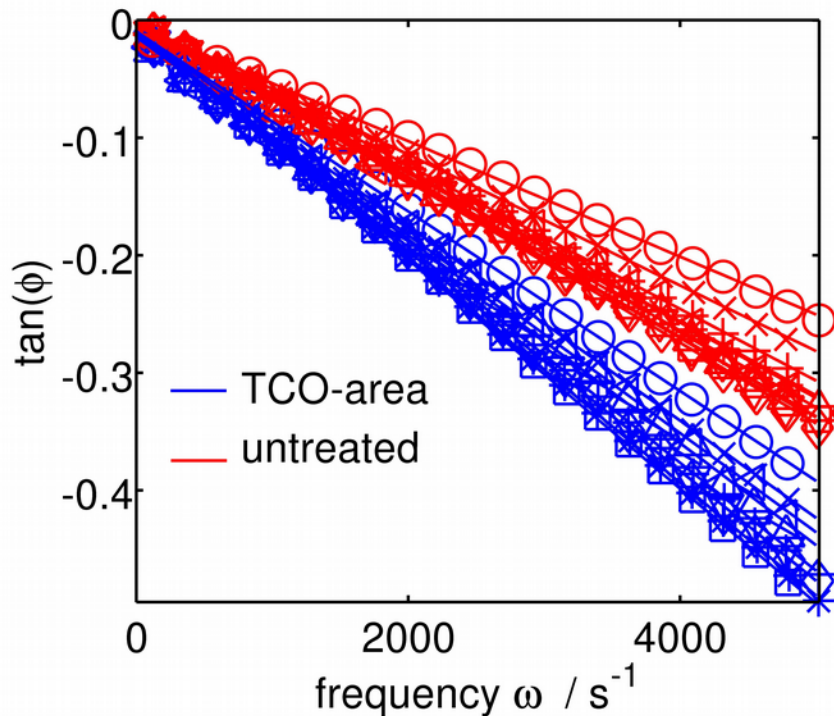
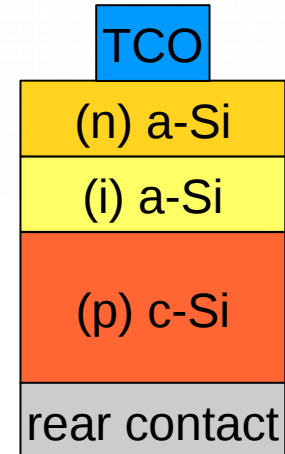
$$\gamma = 2 + 2\beta$$



Results: Cell

a-Si passivated p-type wafer ($1 \Omega\text{cm}$, $N_A = 10^{16} \text{ cm}^{-3}$) with TCO

MPL allows measurement on bare wafer and TCO-texture (via small excitation spot)



Summary

- Modulated photoluminescence promises an efficient method for effective lifetime measurement
- MPL is a useful tool for the investigation of a wide range of species of wafers with any passivation
- Advantage of MPL to other lifetime measurements: phase shift allows also investigation of wafers and cells with high doping and backcontacts